



Large Area Nanogratings

1D, rectangular and hexagonal



Description

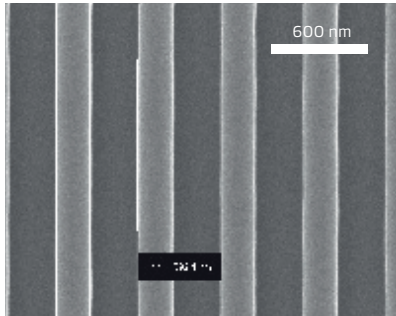
AMO offers gratings fabricated by inhouse interference lithography (IL). The IL technology allows producing large, coherent and periodic gratings with nearly constant pitch. Pattern transfer and further processing can be carried out according to customer requirements. Substrates up to 6 inch and any rectangular within.

Application

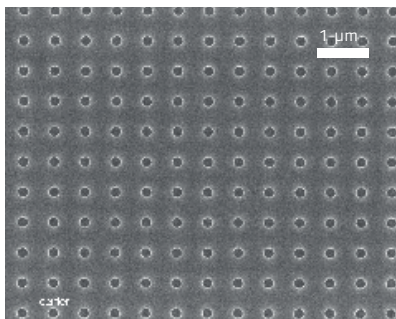
- Master for Imprint Templates
- Microoptics
- NanoBio Technology
- Measurement

Process Control

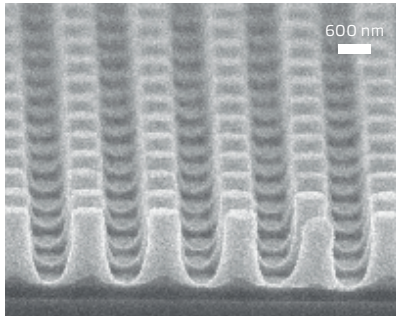
All grating dimensions are specified and controlled during and after processing. Line width maps, LER characterisation and defect inspection are available on request.



Linear Gratings



Hole Pattern



Pillar Pattern



Specification

Substrate material	Silicon or fused silica
Substrate thickness	typical 500 µm to 650 µm
Substrate size	up to 6 inch and any rectangular within
Grating pitch	300 nm to 2.500 nm
Etch depth	90 nm to 2.500 nm
Line width	40 nm to 2.500 nm
Acting grating area	up to 400 mm in diameter

Some specifications are matter of negotiation. For further details please contact us.

Contact

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